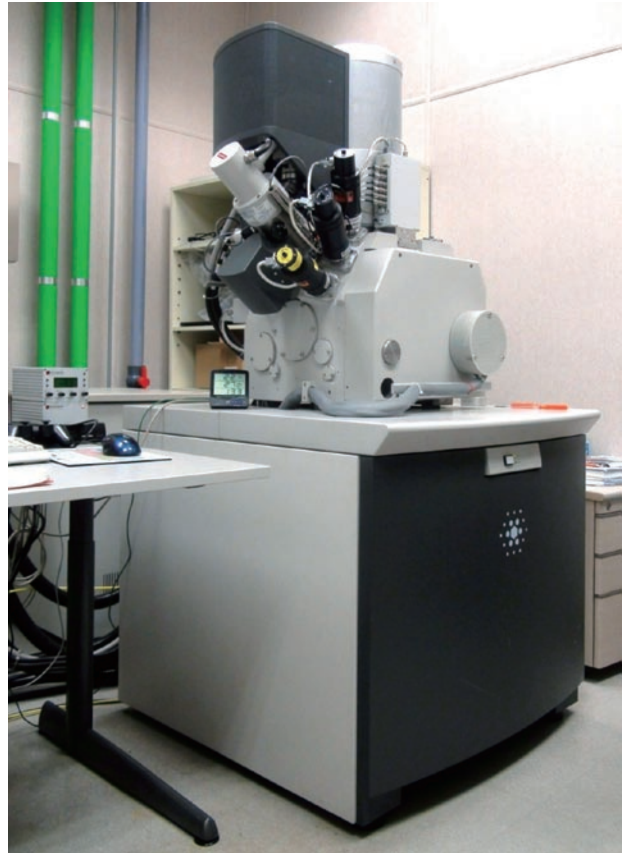
FIB (Nova 600)

집속이온빔

Dual beam Focused Ion Beam has multitude of capabilities including high resolution electron imaging, ion imaging, nano device fabrication and material deposition. Simultaneous patterning and imaging is possible with nm resolution for both imaging and machining. Using software control, digital pattern can be directly applied and unattended operation with high repeatability can be employed for TEM sample preparation.



Location L5115A Tel.02-958-5985

Model

FEI (Nova 600 NanoLab)

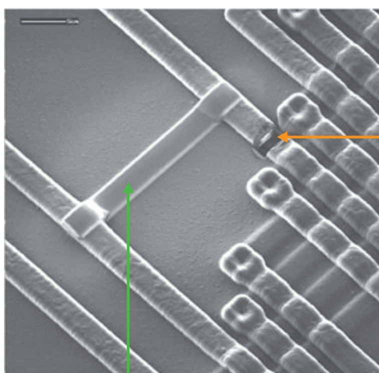
Specifications

- Accelerating voltage : 5 ~ 30 kV
- Image resolution : 1.1 nm (15 kV)
- Magnification : 25 ~ 1,000,000 X
- Stage : 6", Piezo linear motor control

Applications

- SE / BSE / Ion image
- Slice & View
- Nano patlerning

Ion beam machining



TEM sample preparation